

# METHOD AND APPARATUS FOR SIMULATING STANDARD TEST WAFERS

## ABSTRACT OF THE DISCLOSURE

A method and apparatus are provided for simulating a standard wafer in semiconductor manufacturing equipment. The apparatus includes a support layer suitable for being handled by the semiconductor manufacturing equipment. Applied to the support layer is a mixture including a process agent and a material. During use, the present invention simulates a standard production wafer including material similar to that in the mixture of the present invention.

1. A method for simulating a standard wafer in semiconductor manufacturing equipment, comprising: providing a support layer suitable for being handled by the semiconductor manufacturing equipment; and applying a mixture including a process agent and a material to the support layer, wherein during use, the present invention simulates a standard production wafer including material similar to that in the mixture of the present invention.